

Walter E Henderson

List of Publications by Year in descending order

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31
papers

407
citations

840776

11
h-index

752698

20
g-index

31
all docs

31
docs citations

31
times ranked

568
citing authors

#	ARTICLE	IF	CITATIONS
1	Spatially resolved 3D metabolomic profiling in tissues. <i>Science Advances</i> , 2021, 7, .	10.3	29
2	Strain relaxation via formation of cracks in compositionally modulated two-dimensional semiconductor alloys. <i>Npj 2D Materials and Applications</i> , 2018, 2, .	7.9	23
3	Characterization and Simulation of Permittivity Enhancements of SiO ₂ /Si ₃ N ₄ /Nanolaminate Layers. , 2018, , .		0
4	ALD TiO ₂ as a top-gate dielectric and passivation layer for InGaZnO ₁₁₅ ISFETs. <i>Semiconductor Science and Technology</i> , 2017, 32, 114004.	2.0	4
5	A mechanistic study of the interaction of water-soluble borate glass with apatite-bound heterocyclic nitrogen-containing bisphosphonates. <i>Acta Biomaterialia</i> , 2016, 31, 339-347.	8.3	5
6	Impact of Microstructure on Dielectric Nanocomposites With High- <i>k</i> Interfacial Layers. <i>IEEE Nanotechnology Magazine</i> , 2015, 14, 717-725.	2.0	1
7	Using a university characterization facility to educate the public about microscopes: light microscopes to SEM. , 2015, , .		0
8	Fractal Electrode Formation in Metal-Insulator Composites Near the Percolation Threshold. <i>IEEE Nanotechnology Magazine</i> , 2013, 12, 725-733.	2.0	4
9	In situ Auger probe enabling epitaxy composition control of alloys by elemental surface analysis. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2013, 31, 03C126.	1.2	2
10	Halide based MBE of crystalline metals and oxides. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2012, 9, 155-160.	0.8	20
11	A versatile metal-halide vapor chemistry for the epitaxial growth of metallic, insulating and semiconducting films. <i>Journal of Crystal Growth</i> , 2011, 324, 134-141.	1.5	17
12	Growth kinetics of Al _x Ga _{1-x} N grown via ammonia-based metal-organic molecular beam epitaxy. <i>Journal of Crystal Growth</i> , 2010, 312, 209-212.	1.5	3
13	High-Temperature Growth of GaN and Al _x Ga _{1-x} N via Ammonia-Based Metalorganic Molecular-Beam Epitaxy. <i>Journal of Electronic Materials</i> , 2010, 39, 473-477.	2.2	0
14	Complementary oxide memristor technology facilitating both inhibitory and excitatory synapses for potential neuromorphic computing applications. , 2009, , .		12
15	Extremely high hole concentrations in c-plane GaN. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2009, 6, S788.	0.8	27
16	Growth and characterization of Al _x Ga _{1-x} N via NH ₃ -based metal-organic molecular beam epitaxy. <i>Journal of Crystal Growth</i> , 2009, 311, 1328-1332.	1.5	6
17	Transient atomic behavior and surface kinetics of GaN. <i>Journal of Applied Physics</i> , 2009, 106, .	2.5	41
18	Investigation into the use of molecular hydrogen on the growth of gallium nitride via metal-organic molecular beam epitaxy. <i>Physica Status Solidi C: Current Topics in Solid State Physics</i> , 2008, 5, 1723-1725.	0.8	1

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19	Mixed alkyl exchange and exploitable surface interactions in InGaN by NH ₃ -based metal organic molecular beam epitaxy. <i>Journal of Crystal Growth</i> , 2008, 310, 5297-5302.	1.5	4
20	Reclamation of a molecular beam epitaxy system and conversion for oxide epitaxy. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2008, 26, 1501-1506.	2.1	0
21	InN: A material with photovoltaic promise and challenges. <i>Journal of Crystal Growth</i> , 2006, 288, 218-224.	1.5	82
22	An investigation of the effects of radiation exposure on stability constraints in epitaxial SiGe strained layers. <i>Solid-State Electronics</i> , 2006, 50, 1194-1200.	1.4	1
23	Influence of growth conditions and surface reaction byproducts on GaN grown via metal organic molecular beam epitaxy: Toward an understanding of surface reaction chemistry. <i>Journal of Electronic Materials</i> , 2006, 35, 562-567.	2.2	7
24	Molecular Beam Epitaxy of Lithium Niobate Multifunctional Materials Using a Chloride Refractory Metal Chemistry. <i>ECS Transactions</i> , 2006, 2, 103-114.	0.5	3
25	Mg doped GaN using a valved, thermally energetic source: enhanced incorporation, and control. <i>Journal of Crystal Growth</i> , 2005, 279, 26-30.	1.5	18
26	Growth of InN on Ge substrate by molecular beam epitaxy. <i>Journal of Crystal Growth</i> , 2005, 279, 311-315.	1.5	14
27	Molecular beam epitaxy of complex metal-oxides: Where have we come, where are we going, and how are we going to get there?. <i>Journal of Vacuum Science & Technology an Official Journal of the American Vacuum Society B, Microelectronics Processing and Phenomena</i> , 2005, 23, 1272.	1.6	32
28	III-nitride integration on ferroelectric materials of lithium niobate by molecular beam epitaxy. <i>Applied Physics Letters</i> , 2005, 87, 171107.	3.3	34
29	Mg Doped GaN Using a Valved, Thermally Energetic Source: Enhanced Incorporation, Control and Quantitative Optimization. <i>Materials Research Society Symposia Proceedings</i> , 2003, 798, 719.	0.1	4
30	III-Nitride Growth on Lithium Niobate: A New Substrate Material for Polarity Engineering in III-Nitride Heteroepitaxy. <i>Materials Research Society Symposia Proceedings</i> , 2002, 743, L1.4.1.	0.1	11
31	Molecular Beam Epitaxial Growth of AlN/GaN Multiple Quantum Wells. <i>Materials Research Society Symposia Proceedings</i> , 2002, 743, L6.2.1.	0.1	2